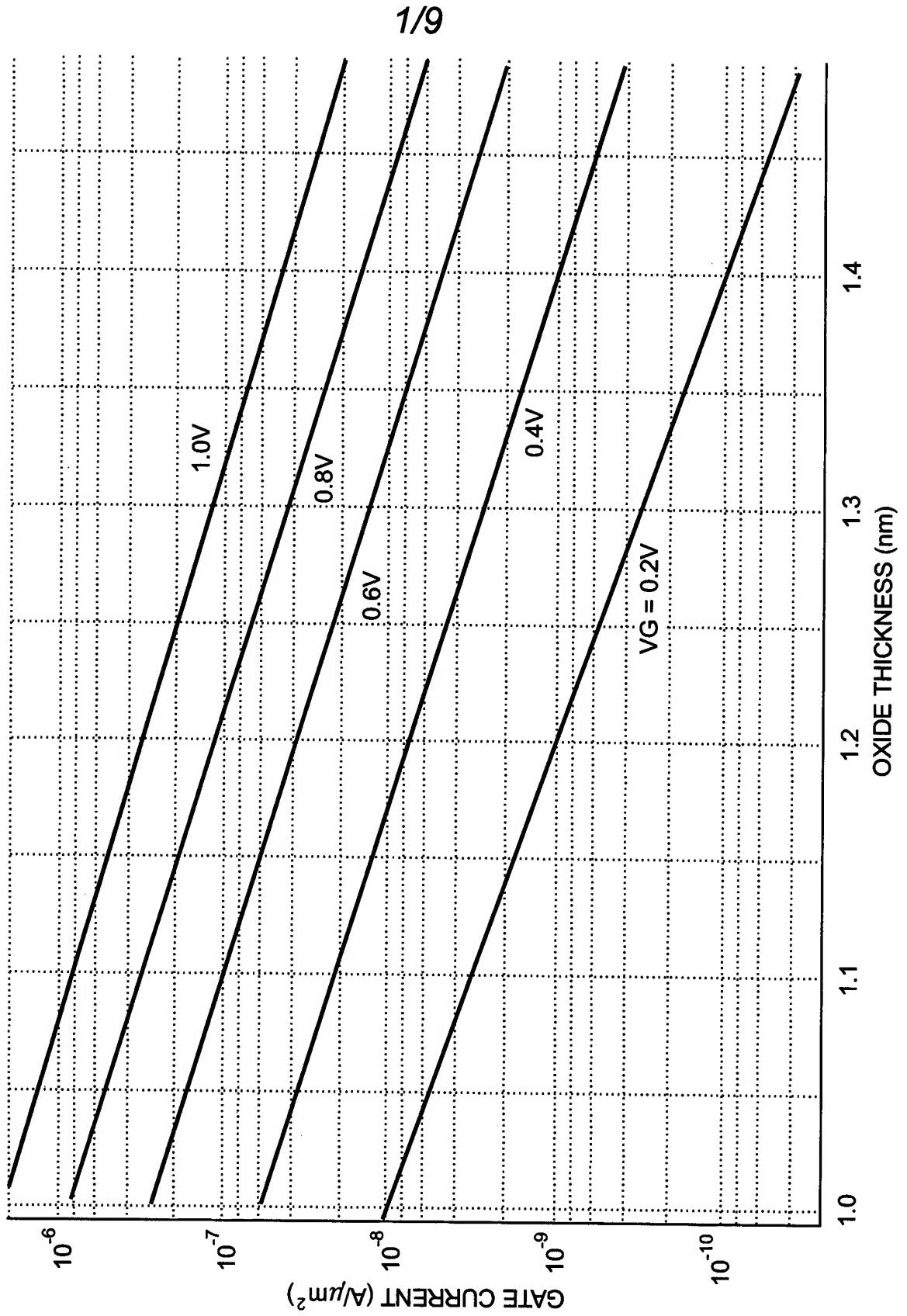
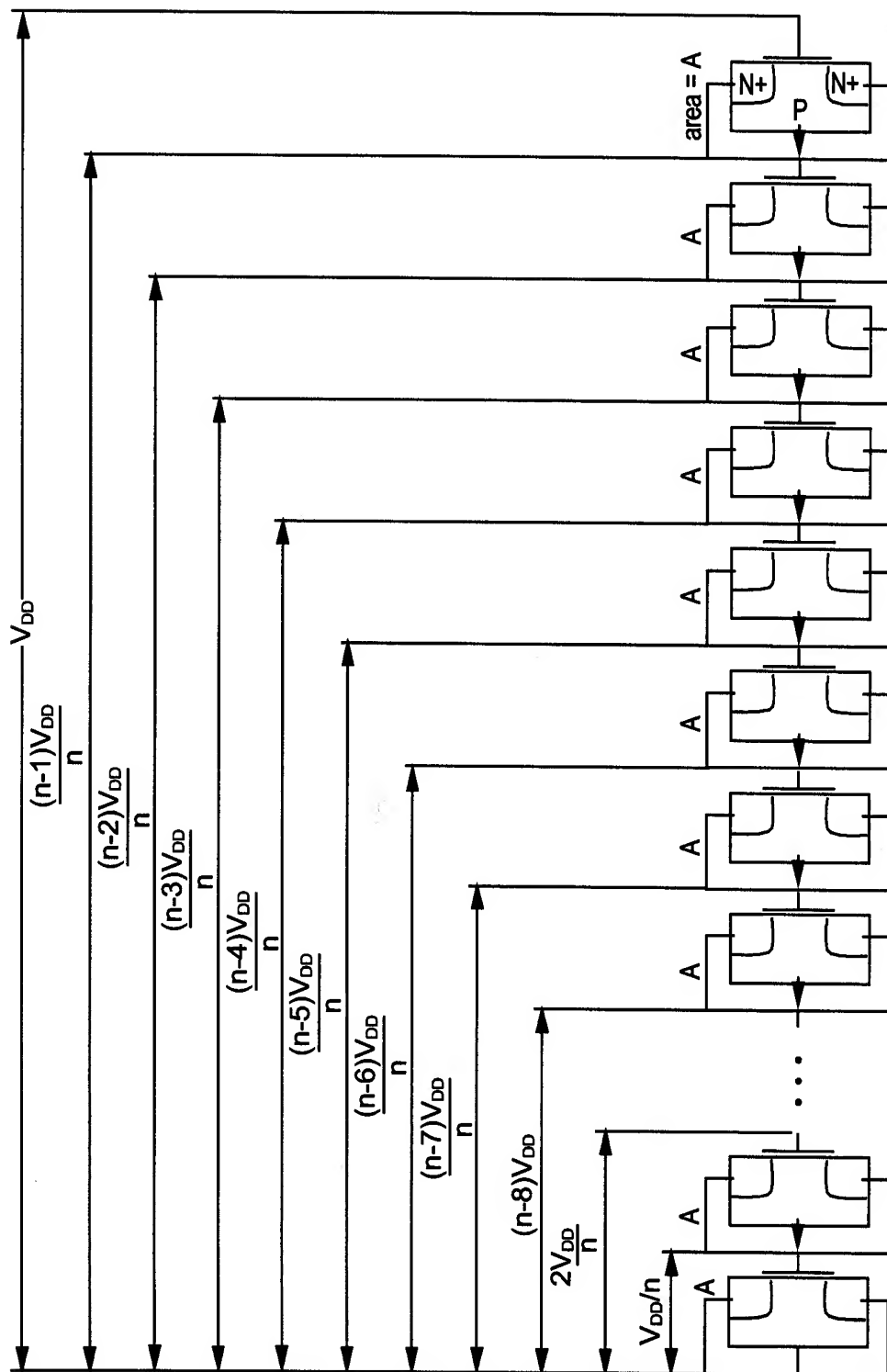


FIG. 1
NFET GATE CURRENT VERSUS OXIDE THICKNESS



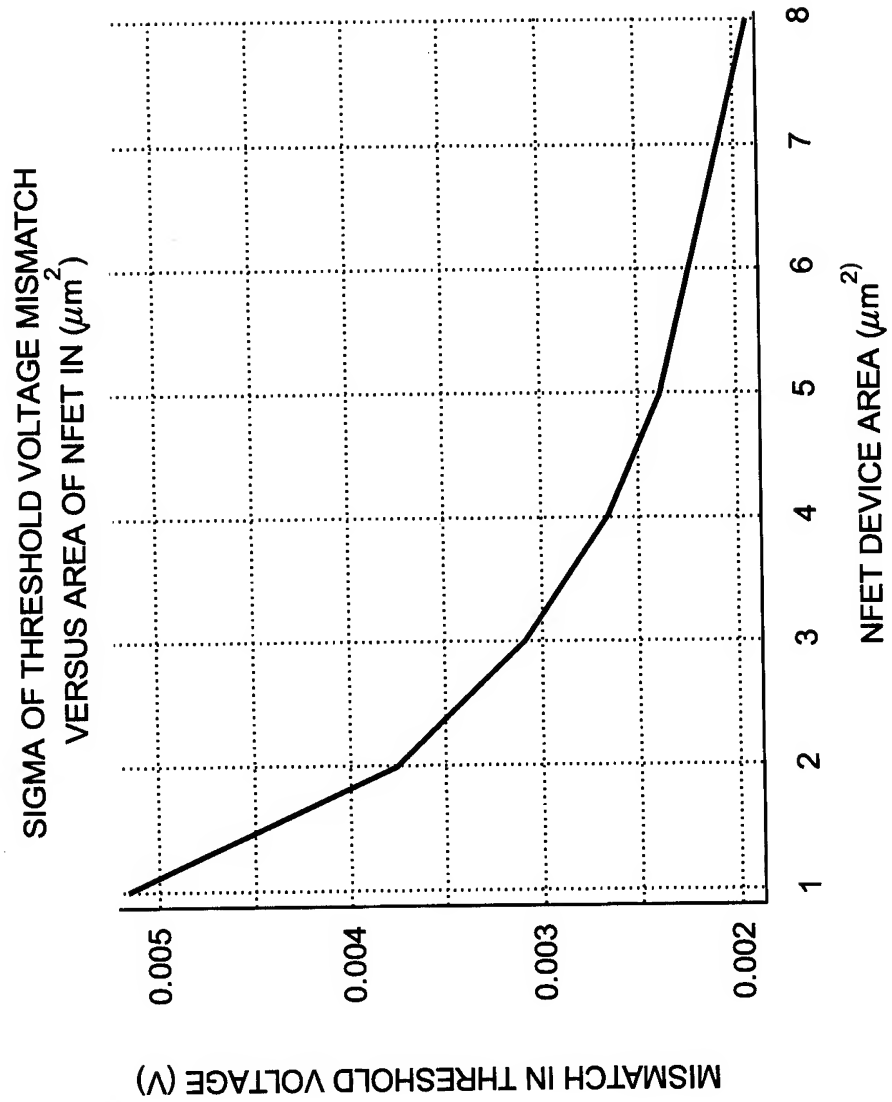
2/9

FIG. 2



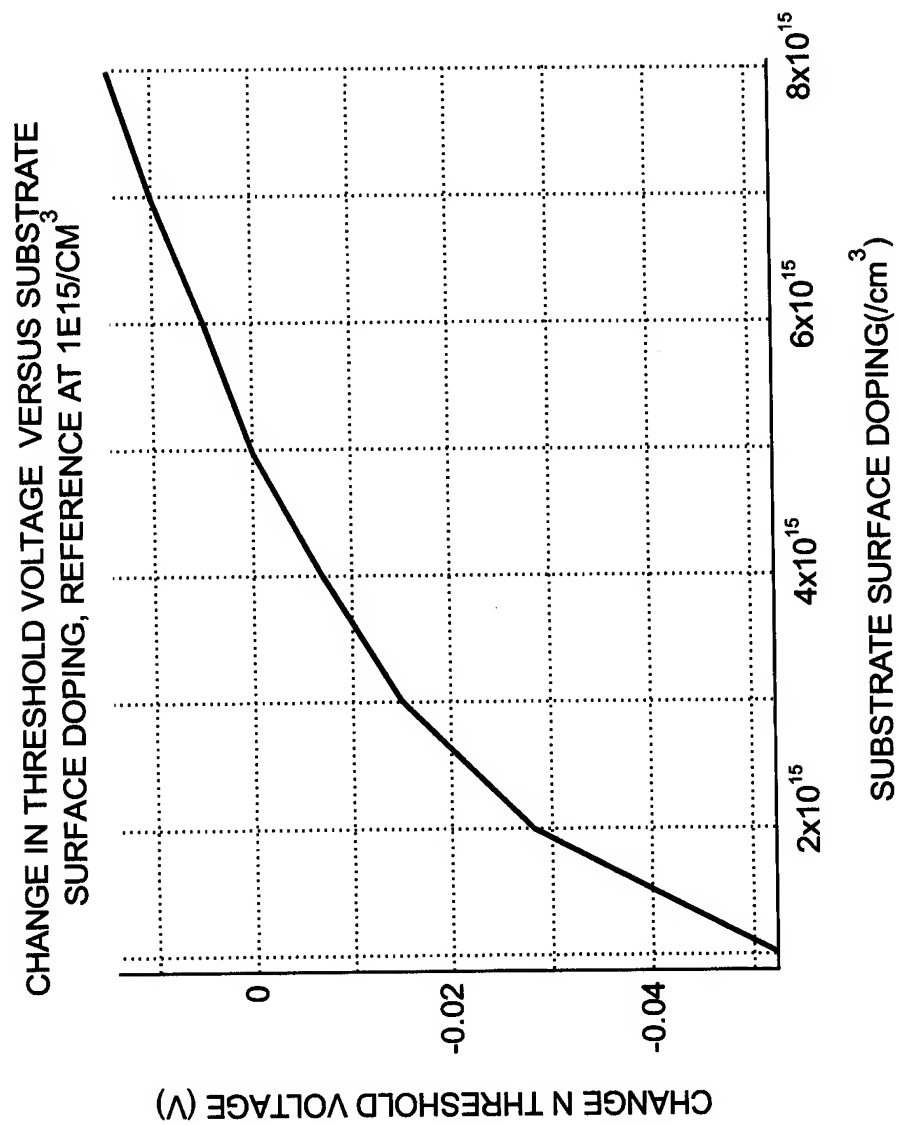
3/9

FIG. 3



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FIG. 4



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FIG. 5

EFFECT OF SUBSTRATE SURFACE DOPING ON
NFET, GATE TUNNELING CURRENT

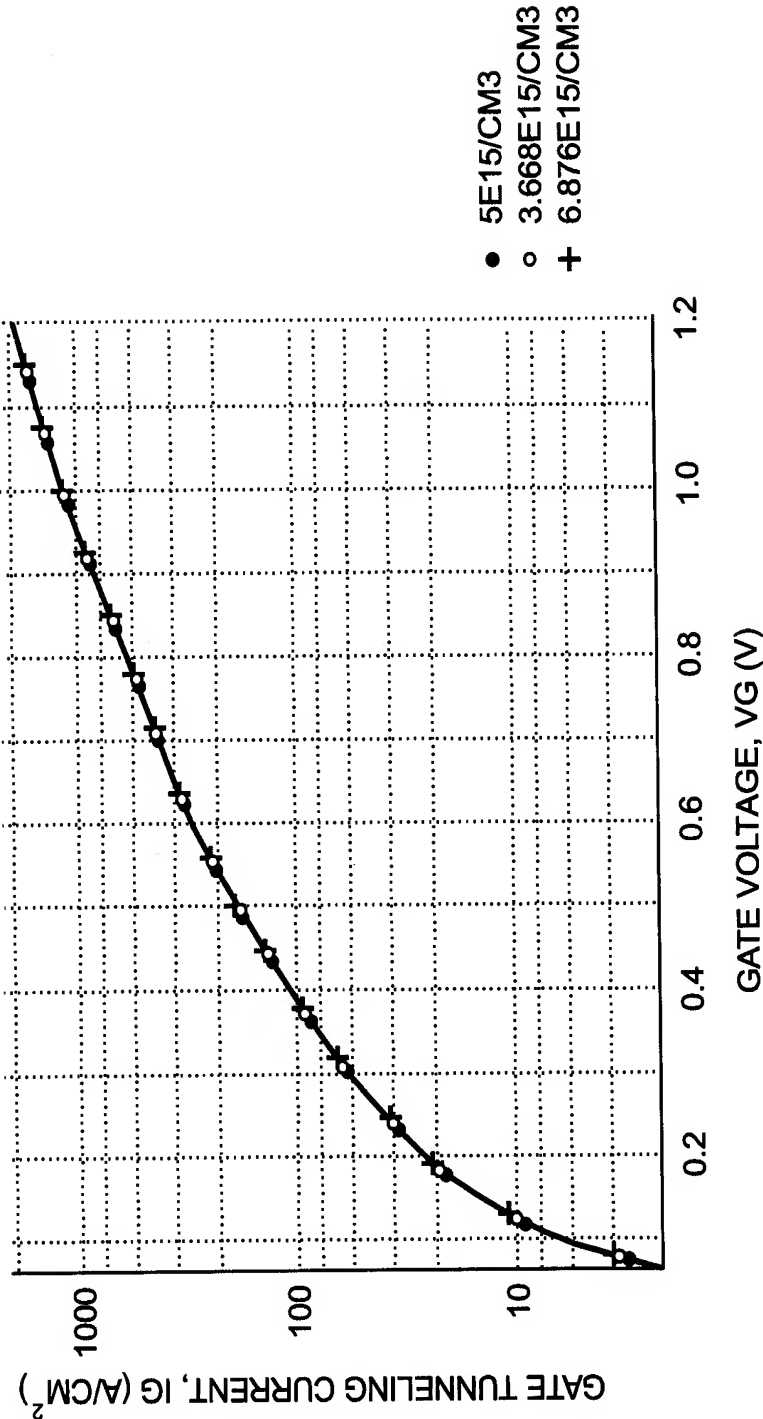


FIG. 6

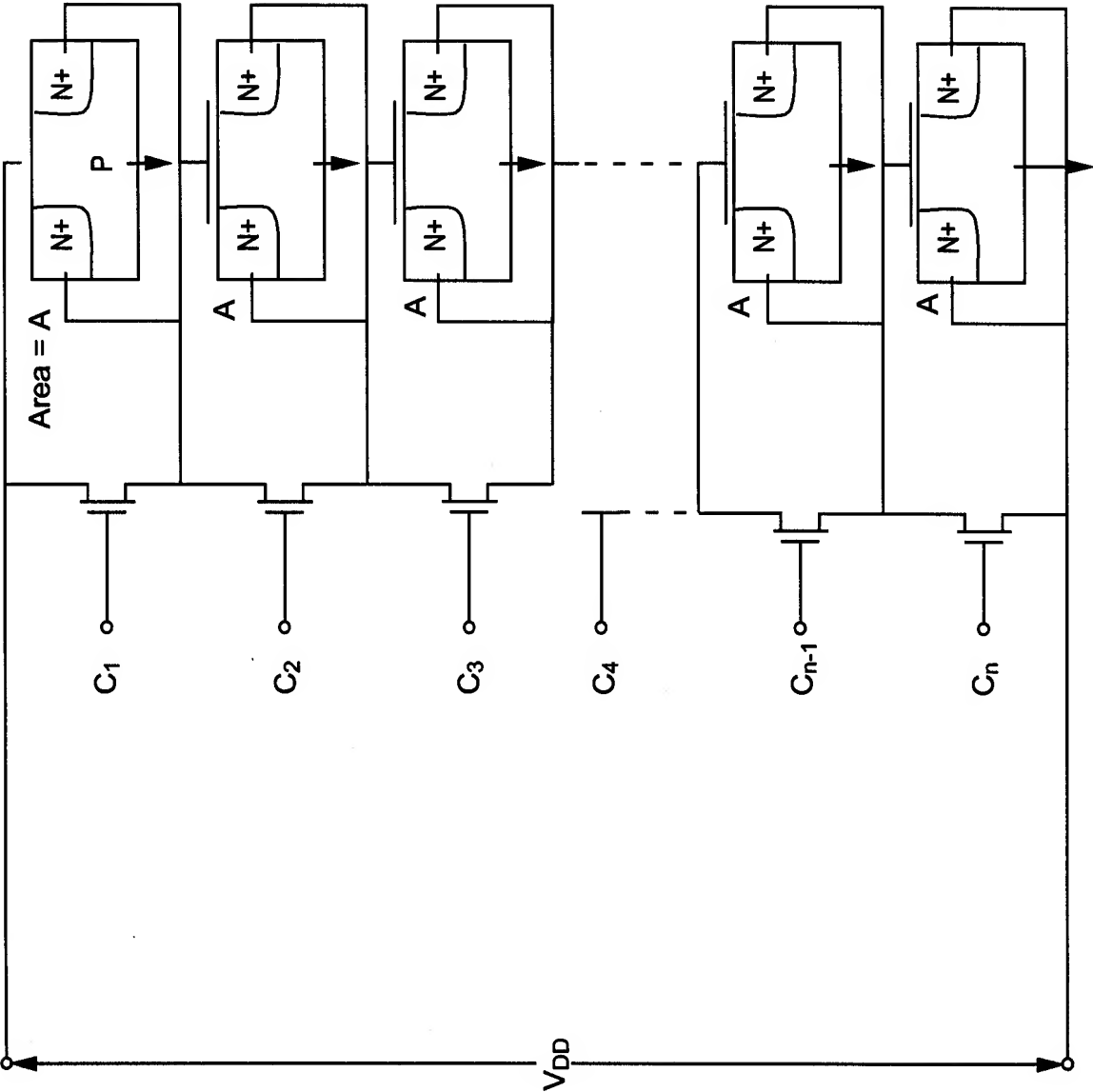


FIG. 7

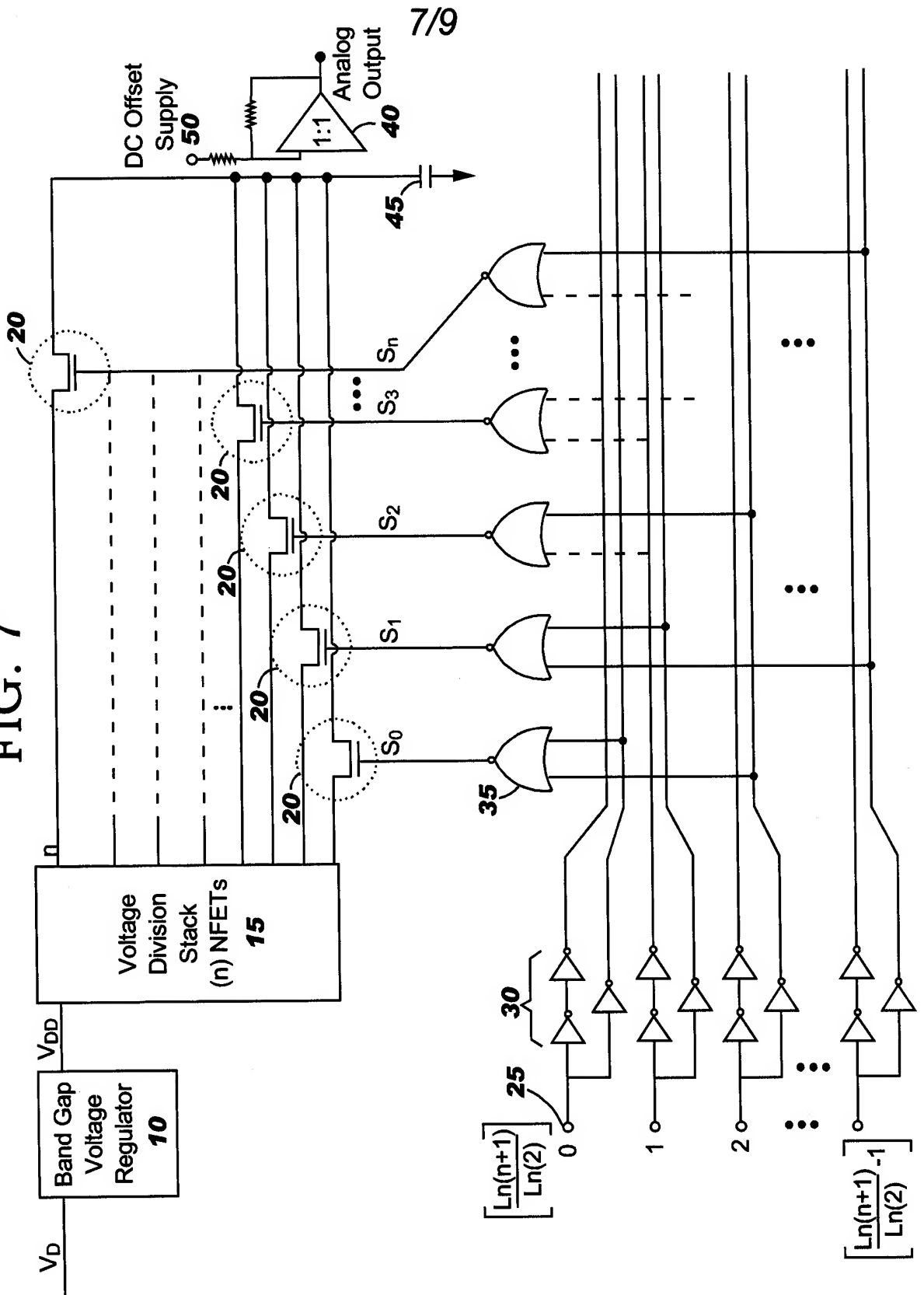
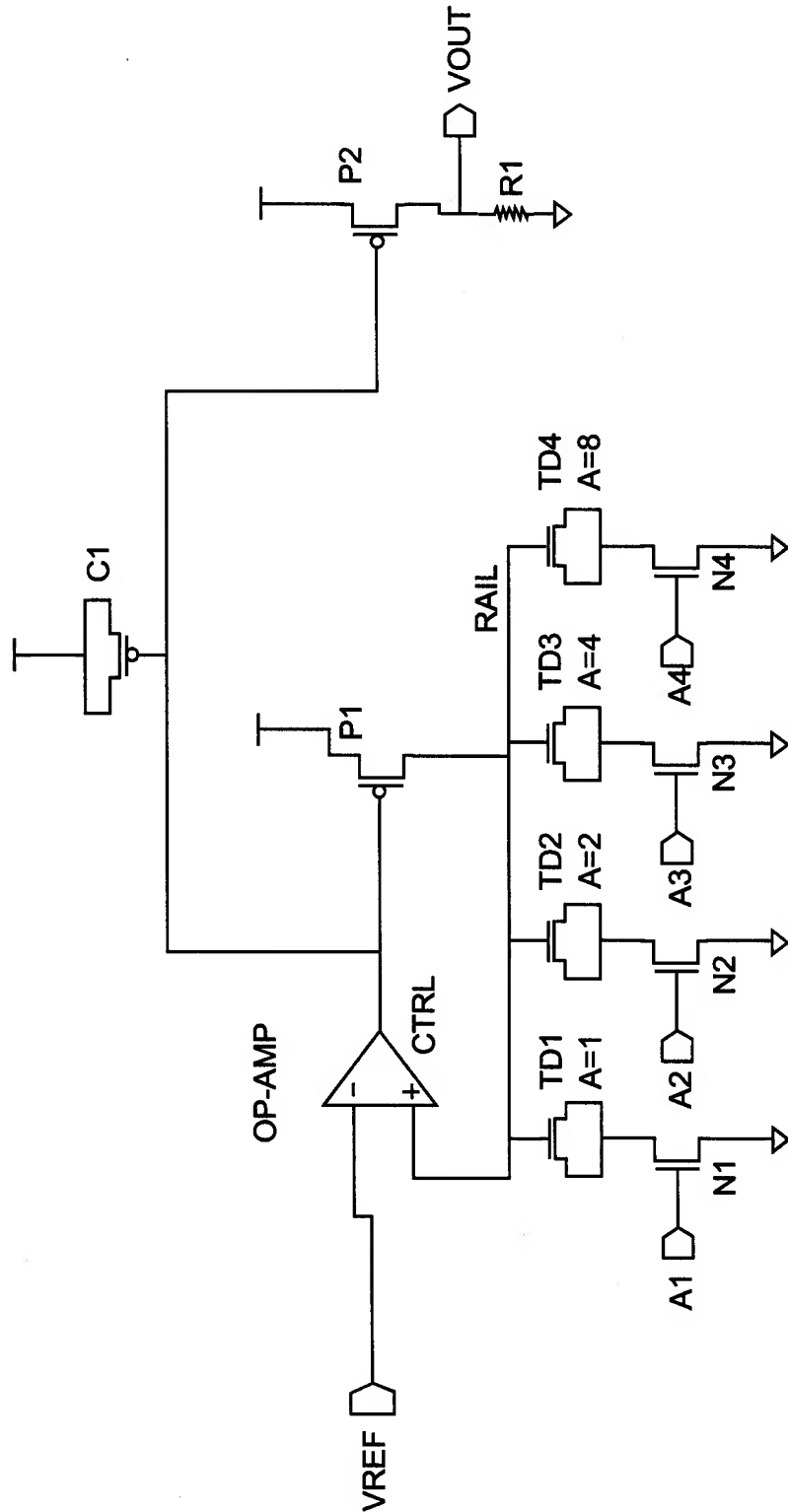


FIG. 8



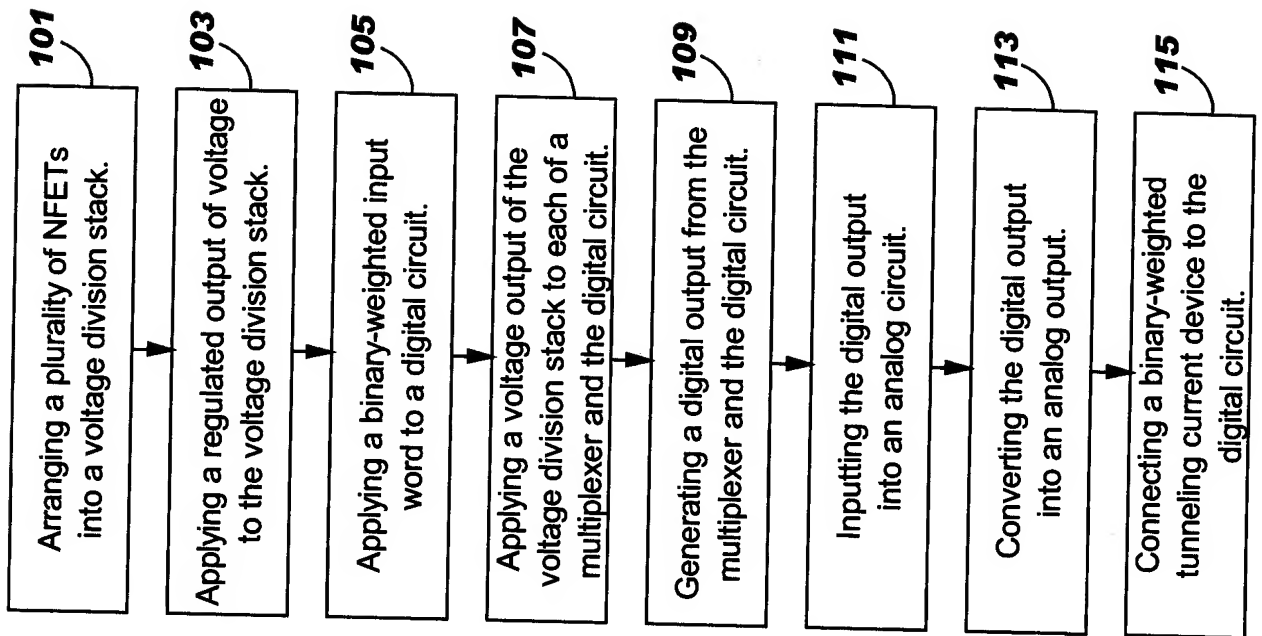


FIG. 9